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# Growth of europium-doped gallium oxide ( $\text{Ga}_2\text{O}_3:\text{Eu}$ ) thin films deposited by homemade DC magnetron sputtering

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## Abstract

Europium-doped gallium oxide ( $\text{Ga}_2\text{O}_3:\text{Eu}$ ) thin films have successfully been grown using direct current magnetron sputtering by means of Eu concentration variation. Energy-dispersive X-ray spectroscopy spectra indicate gallium, oxygen, and europium elements as the growing films' chemical compositions. Based on scanning electron microscopy images, the morphology of  $\text{Ga}_2\text{O}_3:\text{Eu}$  thin film is seemingly like a granulated nano-size configuration. In this study, UV-visible spectrophotometer results show that the variation of Eu doping concentration inflicted no change toward the optical bandgap of the growing films. The optical bandgaps of undoped  $\text{Ga}_2\text{O}_3$  film and  $\text{Ga}_2\text{O}_3:\text{Eu}$  film were seen to be relatively similar, i.e., approximately 3.4 eV. Yet, the presence of Eu doping in  $\text{Ga}_2\text{O}_3$  configuration had led to blueshift phenomenon when the concentration was 2% and redshift phenomenon when it was 5%. Photoluminescence emissions of all samples were observed in the red area with the emission peak between 593 and 602 nm.

**Keywords:**  $\text{Ga}_2\text{O}_3:\text{Eu}$ , DC magnetron sputtering; EDX, SEM, UV-vis spectrophotometer, PL spectrometer

## Background

Gallium oxide ( $\text{Ga}_2\text{O}_3$ ) material has long been a concern by many researchers, engineers, and scientists due to its transparency in ultraviolet range. Its wavelength is recorded up to the areas of 280 nm. Hence,  $\text{Ga}_2\text{O}_3$  material has a high potential to be the new generation of optoelectronic devices applied as transparent conductive oxide [1]. The melting point of  $\text{Ga}_2\text{O}_3$  is around 1,740°C. Thus,  $\text{Ga}_2\text{O}_3$  is considered to be one of the materials that will remain stable at high temperature. The conductivity of  $\text{Ga}_2\text{O}_3$  material depends on the atmospheric environment so that it is suitable for gas sensor application [2].  $\text{Ga}_2\text{O}_3$  material can be applied as passivation material on the gate of field effect transistor because it has a high dielectric constant [3]. Besides,  $\text{Ga}_2\text{O}_3$  is one of the fascinating oxide-based phosphor materials that are physically and chemically more stable than sulfide-based phosphor materials for flat-panel display application [4]. Moreover,  $\text{Ga}_2\text{O}_3$  material has amazing luminescence properties

that make it appropriate to be used as thin-film electroluminescence (TFEL)-based devices [5].

$\text{Ga}_2\text{O}_3$  has extensively been used for luminescent phosphorus application due to its fascinating luminescence properties especially when it is doped with rare earth elements.  $\text{Ga}_2\text{O}_3$  is an oxide-crystal structure with a high anisotropy degree, which has a tetrahedral or octahedral interconnection. It forms a wide tunnel in the crystal. This tunnel is believed to be playing an important role in the process of hot electron transport that is required for electroluminescence emission [6]. Luminescence characteristics of undoped  $\text{Ga}_2\text{O}_3$  were observed in the color spectrum of UV (3.40 eV), blue (2.59 eV), and green (2.48 eV) areas. In order to increase the luminescence intensity of oxide-based phosphor material, Mn and Eu elements were used as dopants to activate luminescence, which produces green and red emissions [5]. Mn is one of the transition elements that have potential for phosphorus luminescence application and TFEL-based devices for its excellent luminescent center. Meanwhile, Eu element is used because it leads to high quantum efficiency and high-speed radiation luminescence of organic materials whenever it is used as a dopant [7].

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$\text{Ga}_2\text{O}_3$  thin film has been grown through various methods, such as metalorganic chemical vapor deposition (MOCVD) [8], MBE [9], floating zone [10], rf magnetron sputtering [11], photoelectrochemical [12], and pulse laser ablation [8]. The film's properties strongly depend on the growth condition, such as chamber partial pressure, substrate temperature, and annealing process pascade-position. In this study,  $\text{Ga}_2\text{O}_3$  is doped by Eu ( $\text{Ga}_2\text{O}_3\text{:Eu}$  thin films) and grown by homemade direct current (DC) magnetron sputtering. DC magnetron sputtering is one of the simple deposition techniques with low operation cost but have stable growth process and high deposition rates. The doping element is given in order to enhance the optical properties of  $\text{Ga}_2\text{O}_3$  film. Eu is chosen as the doping element because of its capability in producing luminescence emission that lies on the red area [5]. This study focused on the investigation of the structural and optical properties of  $\text{Ga}_2\text{O}_3\text{:Eu}$  thin films. Then, the optical properties of  $\text{Ga}_2\text{O}_3\text{:Eu}$  thin films will be compared with the optical properties of undoped  $\text{Ga}_2\text{O}_3$  thin film.

## Results and discussion

In order to find out if only Eu element can be doped and deposited together with  $\text{Ga}_2\text{O}_3$  on the substrate surface, the experiment was carried out using  $\text{Ga}_2\text{O}_3\text{:Eu}$  (5%) pellet as target. The film was grown on Si(100) substrate. The deposition temperature, plasma power, argon pressure, oxygen pressure, and deposition time were set at 600°C, 40 W, 600 mTorr, 100 mTorr, and 3 h, respectively. The grown sample was characterized using energy-dispersive X-ray spectroscopy (EDX), and its spectra are shown in Figure 1. The occurrence of oxygen (O), gallium (Ga), and europium (Eu) on the growing film, based on EDX analysis, indicated that Eu-doped  $\text{Ga}_2\text{O}_3$

thin film has been successfully grown on Si(100) substrate using DC magnetron sputtering. This result is in line with the findings found in some previous studies regarding XRD analysis [13,14].

The morphology of  $\text{Ga}_2\text{O}_3\text{:Eu}$  thin films was investigated using scanning electron microscopy (SEM). The films were grown in two target variations. Those were  $\text{Ga}_2\text{O}_3\text{:Eu}$ (2%) and  $\text{Ga}_2\text{O}_3\text{:Eu}$ (5%). Figure 2 shows SEM images of  $\text{Ga}_2\text{O}_3\text{:Eu}$  thin films grown with Eu-doped variation. SEM images show that the morphology of  $\text{Ga}_2\text{O}_3\text{:Eu}$  thin film was seemingly like a granulated nano-size configuration [15].  $\text{Ga}_2\text{O}_3\text{:Eu}$ (2%) thin film grew up in a high density of identical granulated nano-size, which made it have a relatively smooth surface morphology as shown in Figure 2a. In contrast, the bigger granulated configuration with rough surface morphology was observed on  $\text{Ga}_2\text{O}_3\text{:Eu}$ (5%) thin film as shown in Figure 2b. The roughness of the surface morphology and the grain size of the growing films are likely related to the concentration of Eu element that was deposited. As the surface's roughness and the uniformity of grain size have been believed to be the parameters that determine the growing film's crystal quality, thus,  $\text{Ga}_2\text{O}_3\text{:Eu}$  (2%) thin film was then considered to have a higher crystalline quality than  $\text{Ga}_2\text{O}_3\text{:Eu}$ (5%) thin film.

Generally, the surface morphology of the thin film has a great relationship with the crystal quality of the film itself. By introducing Eu element on  $\text{Ga}_2\text{O}_3$  host material, it was expected that it will be able to stimulate the transformation structure from a single crystal to poly-crystal structures. The  $\text{Ga}_2\text{O}_3\text{:Eu}$  thin film that was grown was noted to have a granulated configuration with a single orientation. Therefore,  $\text{Ga}_2\text{O}_3\text{:Eu}$  thin film has a low degree of magnetic anisotropy but a high magnetic permeability degree. Based on this characteristics,  $\text{Ga}_2\text{O}_3\text{:Eu}$

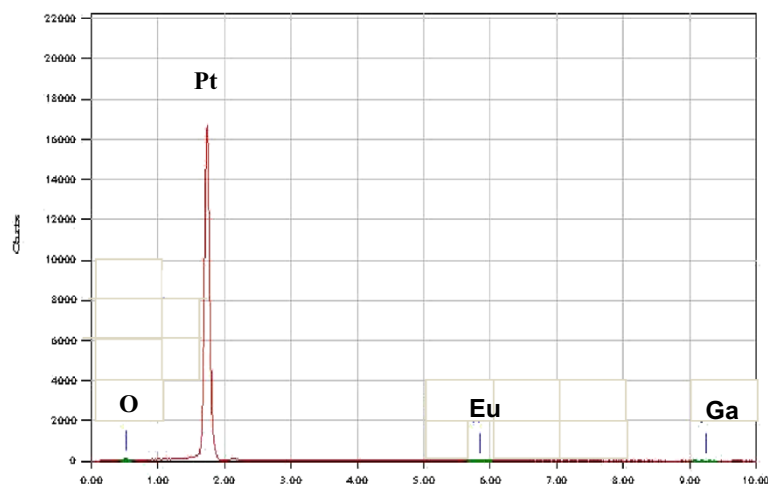
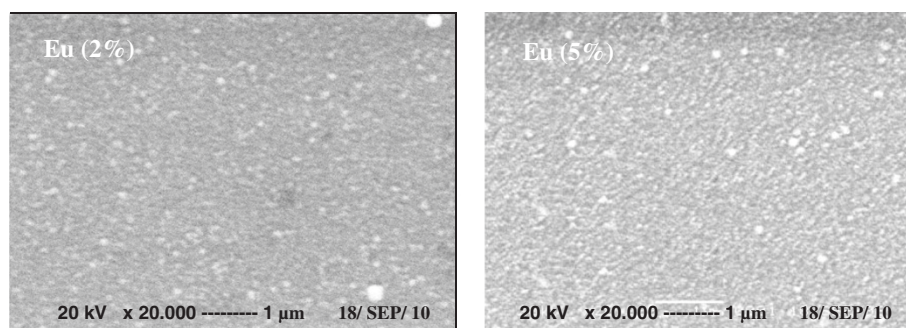


Figure 1 EDX spectra of  $\text{Ga}_2\text{O}_3\text{:Eu}$  (5%) thin film.



**Figure 2** SEM images of (a)  $\text{Ga}_2\text{O}_3:\text{Eu}$  (2%) and (b)  $\text{Ga}_2\text{O}_3:\text{Eu}$ (5%) thin films grown on Si(100).

film is then viewed to be suitable for TFEL device application. In comparison to the undoped  $\text{Ga}_2\text{O}_3$  thin film that has been grown by Sugianto et al.,[13], the surface morphology of  $\text{Ga}_2\text{O}_3:\text{Eu}$  thin films is smoother. It has a smaller grain size, and the distribution of the grains on the surface of the substrate seems to be more uniform [13]. As a consequence, it can be concluded that the existence of Eu(2%) atoms on  $\text{Ga}_2\text{O}_3$  thin film will lead to smoothing effect on the surface morphology of the thin film. However, it can be noted as well that the rising concentration of Eu did not significantly change the surface morphology of  $\text{Ga}_2\text{O}_3$  thin films.

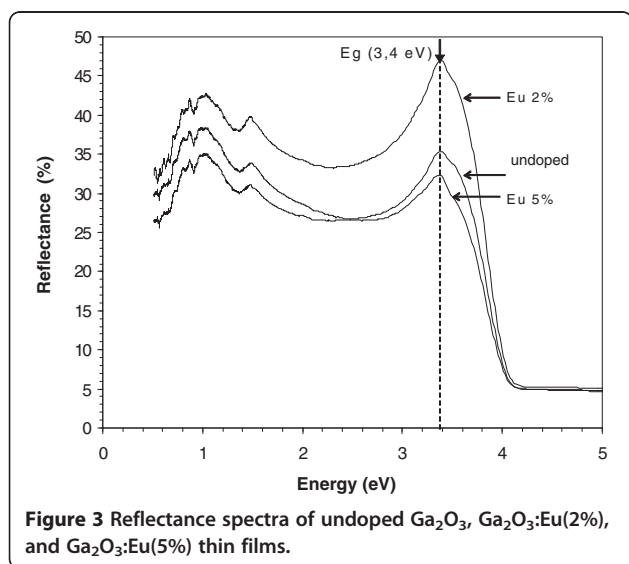
The optical properties of  $\text{Ga}_2\text{O}_3:\text{Eu}$ (2%) and  $\text{Ga}_2\text{O}_3:\text{Eu}$ (5%) thin films have been analyzed using room-temperature UV-nir spectrophotometer in the wavelength range of 200 to 2,400 nm. The reflectance spectra of Eu-doped  $\text{Ga}_2\text{O}_3$  thin films were then been compared with the reflectance spectra of undoped  $\text{Ga}_2\text{O}_3$  film [14] as shown in Figure 3. The reflectance pattern of all films was basically similar. It meant that the presence of Eu doped on  $\text{Ga}_2\text{O}_3$  host material did not change the

reflectance pattern but contributed in changing the intensity of the reflectance spectra. It can be seen afterward that  $\text{Ga}_2\text{O}_3:\text{Eu}$ (2%) thin film has the highest spectra intensity, followed by undoped  $\text{Ga}_2\text{O}_3$  film. Surprisingly, the rising of Eu doping concentration from 2% to 5% decreases the reflectance intensity of  $\text{Ga}_2\text{O}_3:\text{Eu}$  (5%) film instead. This phenomenon is believed to occur due to the surface morphology effect of the thin film, which was discussed previously based on SEM observation results.

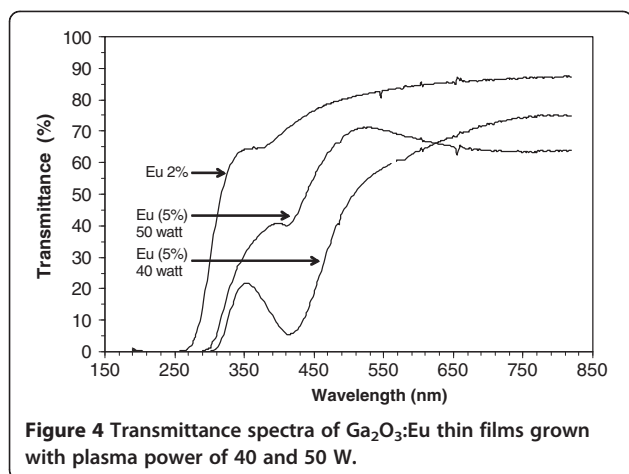
The reflectance spectra in Figure 3 show the existence of oscillations in each films in the reflectance spectra below 3.4 eV, which is associated with the interference of light in the  $\text{Ga}_2\text{O}_3$  layer [16]. Furthermore, based on Figure 3, it can be estimated that the value of optical bandgap ( $E_g$ ) of  $\text{Ga}_2\text{O}_3$  film was around 3.4 eV, related to the band-to-band absorption. This value is similar with the photoluminescence (PL) characterization result of undoped  $\text{Ga}_2\text{O}_3$  thin film that was reported by Villora et al. [17]. They reported that the luminescence peak of undoped  $\text{Ga}_2\text{O}_3$  film was observed in the UV area of 3.40 eV [17].

Based on the theoretical approach, the bandgap of  $\text{Ga}_2\text{O}_3$  materials should be 2.71 eV [18], whereas from the experiment results, it varies depending on the growth conditions (parameters) and the substrate. The bandgap of  $\text{Ga}_2\text{O}_3$  films that were grown on fused silica disks under oxygen flow with electron beam evaporation method is recorded as 4.4 eV [19]. Besides, Villora et al. reported that the bandgap of  $\text{Ga}_2\text{O}_3$  thin film grown by floating zone method is around 4.8 eV [20].

$\text{Ga}_2\text{O}_3:\text{Eu}$  thin films grown on corning glass (transparent substrate) at a plasma power of 40 W were analyzed using UV-visible (vis) spectrometer in the wavelength range of 200 to 850 nm as shown in Figure 4. Based on Figures 3 and 4, it can be seen that  $\text{Ga}_2\text{O}_3:\text{Eu}$ (2%) thin films had both the highest transmittance intensity and reflectance intensity as compared to all samples.  $\text{Ga}_2\text{O}_3:\text{Eu}$ (5%) thin films that were grown with the same growth condition have lower transmittance intensity, but when



**Figure 3** Reflectance spectra of undoped  $\text{Ga}_2\text{O}_3$ ,  $\text{Ga}_2\text{O}_3:\text{Eu}$ (2%), and  $\text{Ga}_2\text{O}_3:\text{Eu}$ (5%) thin films.

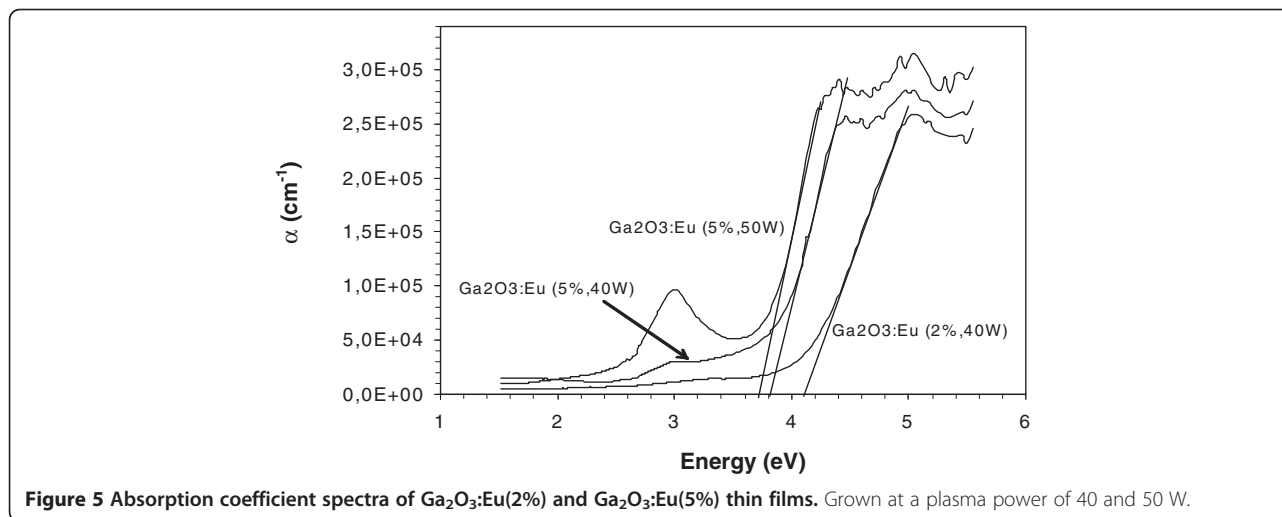


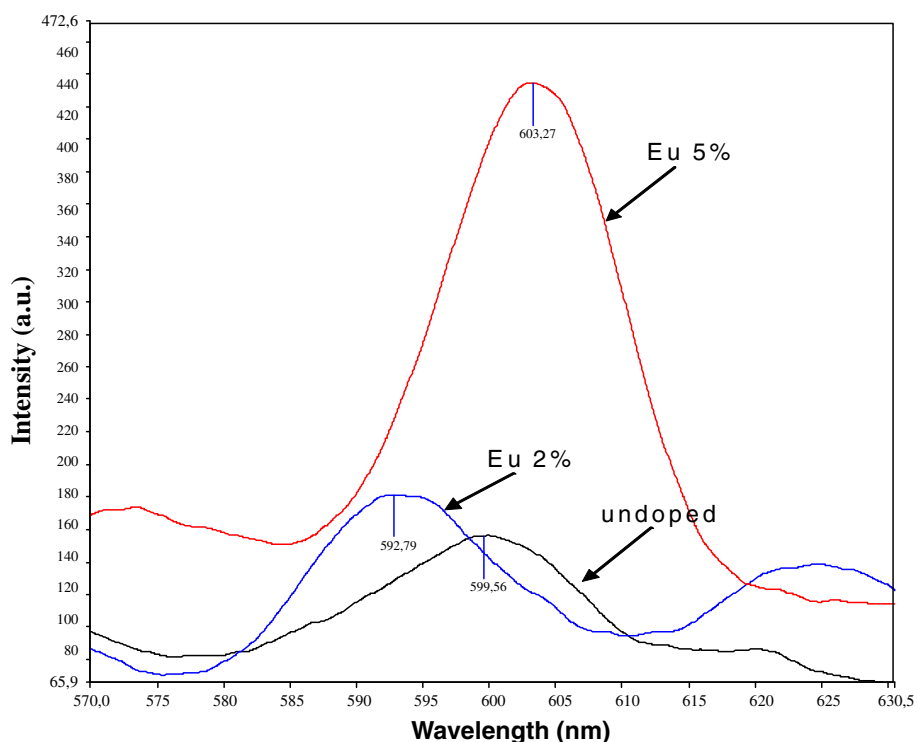
the plasma power was increased to 50 W, its transmittance intensity was increasing although it was still lower than the intensity of  $\text{Ga}_2\text{O}_3:\text{Eu}(2\%)$  film.

The optical absorption spectra of  $\text{Ga}_2\text{O}_3:\text{Eu}$  thin film which functions as photon energy is shown in Figure 5. It can be seen that when  $\text{Ga}_2\text{O}_3:\text{Eu}(2\%)$  film was grown with a plasma power of 40 W, it has absorption edge on the absorption spectra of approximately 3.8 eV, which is related to the band-to-band transition, whereas when  $\text{Ga}_2\text{O}_3:\text{Eu}(5\%)$  thin film was grown with a plasma power of 40 W, its absorption edge was observed at approximately 2.1 and approximately 3.5 eV. Then, when the plasma power was increased to 50 W, the absorption edge of  $\text{Ga}_2\text{O}_3:\text{Eu}(5\%)$  film was clearly observed at approximately 2.4 eV (green region) and approximately 3.5 eV (UV area) with the absorption peak of approximately 3 eV. The band edge (2.1 and 2.4 eV) of  $\text{Ga}_2\text{O}_3:\text{Eu}(5\%)$  film that was grown with a plasma power of 40 and 50 W, respectively, indicate the occurrence of band

tails on the  $\text{Ga}_2\text{O}_3:\text{Eu}(5\%)$  bandgap. The localized band tails of  $\text{Ga}_2\text{O}_3:\text{Eu}(5\%)$  thin film are similar with the experimental result of the previous study by Robertson [21]. It is believed that the band tail occurs due to the existence of defects, which is raising up from the abundance of Eu doping on the  $\text{Ga}_2\text{O}_3:\text{Eu}$  configuration. It is also believed that the abundance of Eu doping leads to crystallographic transformation from crystal structure to amorphous structure. Kim and Kim reported that  $\text{Ga}_2\text{O}_3$  thin films grown by MOCVD method have an amorphous structure [16]. Hence, it can be said that the introduction of Eu doping with a concentration of 5% on the  $\text{Ga}_2\text{O}_3$  material leads to the formation of amorphous structure. Consequently,  $\text{Ga}_2\text{O}_3:\text{Eu}(5\%)$  thin film grew with low crystallinity quality. It can be seen that  $\text{Ga}_2\text{O}_3:\text{Eu}(5\%)$  thin film that was deposited at a plasma power of 50 W has defects spectra starting from the energy area of approximately 2.4 eV and concentrated in the energy area of approximately 3 eV with higher defects intensity compared with the  $\text{Ga}_2\text{O}_3:\text{Eu}(5\%)$  film grown with a plasma power of 40 W. Thus, it can be concluded that the increasing plasma power leads to the increasing degree of crystal defect in the thin film. The absorption edge at the energy range of approximately 3.5 to approximately 4 eV agrees with the energy gap which has been obtained from the reflectance spectrum as shown in Figure 3.

Figure 6 shows PL spectra of  $\text{Ga}_2\text{O}_3:\text{Eu}(2\%)$  and  $\text{Ga}_2\text{O}_3:\text{Eu}(5\%)$  thin films with excitation wavelength of 203 nm, which was compared with PL spectra of undoped  $\text{Ga}_2\text{O}_3$  film as reference. It can be seen that all of the thin films emit the photoluminescence spectra on the red color region. Based on the luminescence spectra, it can be noted that the luminescence peaks of  $\text{Ga}_2\text{O}_3:\text{Eu}(2\%)$ ,  $\text{Ga}_2\text{O}_3:\text{Eu}(5\%)$ , and undoped  $\text{Ga}_2\text{O}_3$  films were at wavelengths of 599 nm (approximately 2.1 eV), 602 nm





**Figure 6** Photoluminescence spectra of undoped  $\text{Ga}_2\text{O}_3$ ,  $\text{Ga}_2\text{O}_3\text{:Eu}(2\%)$ , and  $\text{Ga}_2\text{O}_3\text{:Eu}(5\%)$  thin films.

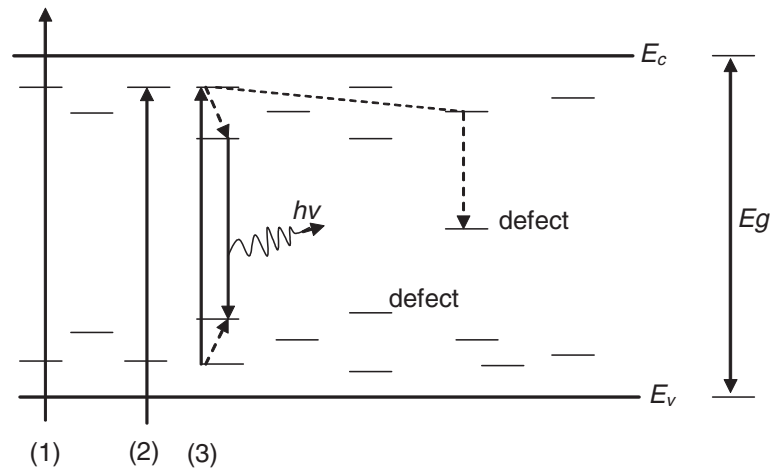
(approximately 2.06 eV), and 593 nm (approximately 2.1 eV), respectively.  $\text{Ga}_2\text{O}_3\text{:Eu}(5\%)$  thin film has the highest intensity at a wavelength of 602 nm, which is related to the electron transition of  $\text{Eu}^{3+}$  [22], followed by  $\text{Ga}_2\text{O}_3\text{:Eu}(5\%)$  film, then by undoped  $\text{Ga}_2\text{O}_3$  thin film. The luminescence peak of  $\text{Ga}_2\text{O}_3\text{:Eu}$  thin film is associated with the electron transition of  ${}^5\text{D}_0 \rightarrow {}^7\text{F}_2$  for  $\text{Eu}^{3+}$  [4]. It can be seen that the luminescence intensity of  $\text{Ga}_2\text{O}_3\text{:Eu}$  film is proportional to the Eu doping concentration. The luminescence intensity can be increased by increasing the concentration of Eu doping (mole fraction of the Eu element). This phenomenon is similar to the luminescence spectra of  $\text{Ga}_2\text{O}_3\text{:Mn}$  thin film that was reported by Kim and Kim [4], in which the luminescence intensity is increased by increasing Mn doping. It is then recorded that  $\text{Mn}^{2+}$  ( $3d^5$ ) ions, which are introduced into  $\text{Ga}_2\text{O}_3\text{:Mn}$  (host material), behave as the luminescence activator in the  $\text{Ga}_2\text{O}_3\text{:Mn}$  material [22]. Therefore, it can be said that the emission intensity depends on the concentration of Eu doping.

Although it does not give a significant effect, the presence of  $\text{Eu}(2\%)$  doping in the  $\text{Ga}_2\text{O}_3$  material leads to the luminescence peak of the film, which tends to shift to a shorter wavelength. Hence, it is considered to be a blueshift phenomenon. In contrast, the luminescence peak shift to the longer wavelength when the Eu doping was increased to 5% was called as redshift phenomenon.

The shifting of photoluminescence peak is generally caused by lattice distortion and relaxation of the charge carrier into deep-gap-states condition before recombination process happens. Nevertheless, this phenomenon is slightly different from the luminescence shifting of  $\text{Ga}_2\text{O}_3\text{:Mn}$  thin film. In the case of  $\text{Ga}_2\text{O}_3\text{:Mn}$  thin film, higher concentration of Mn doping in the  $\text{Ga}_2\text{O}_3$  material will increase the lattice strain. Variation of lattice strain in the  $\text{Ga}_2\text{O}_3\text{:Mn}$  material causes crystal field variations around  $\text{Mn}^{2+}$  elements region [22].  $\text{Mn}^{2+}$  crystal field with weak intensity would lead emission shifting band to the shorter wavelength region, which will result in a wider bandgap (energy gap  $E_g$  is inversely proportional to the wavelength  $\lambda$ ). Thus, it can be said that the emission band of  $\text{Mn}^{2+}$  was slightly shifting due to the effect of variation of crystal field. Besides, in correlation with charge carrier relaxation in the luminescence shifting, it is believed that the presence of Mn atom in the Ga-O configuration leads to the relaxation of Ga-O bonding and stressing of the bandgap. As a result, the energy bandgap of luminescence spectra becomes wider. Meanwhile, in the case of  $\text{Ga}_2\text{O}_3\text{:Eu}$  thin film, the emission characteristic of  $\text{Eu(III)}$  is produced by means of electric dipole transition [4].

It can be seen that the emission intensity of  $\text{Ga}_2\text{O}_3$  thin film luminescence spectra (at approximately 2.1 eV) was lower than the peak intensity of optical bandgap of

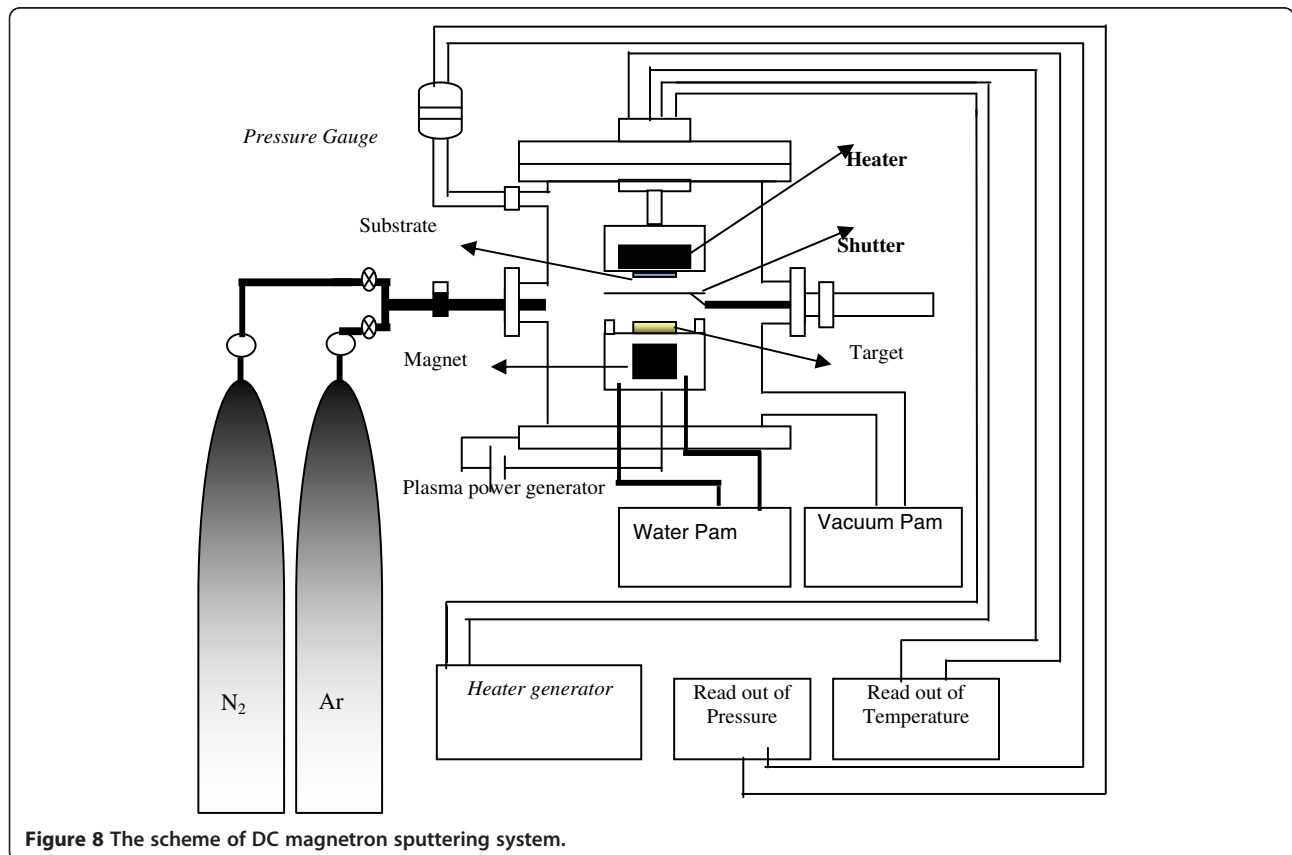




**Figure 7** Three possible pathways of photoluminescence mechanisms. (1) Band-to-band transition, (2) band-to-defect transition, and (3) defect-to-defect transition.

the reflectance spectra (at 3.4 eV). It confirmed that the optical transitions did not occur due to band-to-band transition but because of the defect-to-defect hopping mechanism, which was dominant at the energy distance of approximately 2.1 eV. These defects act as trap in the band tail of the bandgap. Besides the effect of Eu doping, defects can also occur due to the breaking of Ga-O

bonding during deposition process. Based on Figure 6, it can be noted that the photoluminescence peak of all films was around of 2.1 eV. This value agrees with the absorption band edge of  $\text{Ga}_2\text{O}_3:\text{Eu}$  thin films as shown in Figure 4. Previous researchers also reported similar results. Hao et al. reported that  $\text{Ga}_2\text{O}_3:\text{Eu}$  thin film grown by spray pyrolysis method also produced luminescence



**Figure 8** The scheme of DC magnetron sputtering system.

emission in the range of red color with an emission peak of approximately 2.1 eV [4]. Kim and Kim have also reported that the luminescence peak of Ga<sub>2</sub>O<sub>3</sub> thin film grown by MOCVD was at a wavelength of 457 nm (2.71 eV) [15]. In general, three possible pathways of photoluminescence mechanism are shown in Figure 7.

## Conclusions

Ga<sub>2</sub>O<sub>3</sub>:Eu thin films have successfully been grown using DC magnetron sputtering. EDX result shows that the grown film contains Ga, O, and Eu elements. It means that Eu-doped Ga<sub>2</sub>O<sub>3</sub> thin film has been successfully grown. SEM images show that the morphology of Ga<sub>2</sub>O<sub>3</sub>:Eu thin film is seemingly like a granulated nano-size configuration. Ga<sub>2</sub>O<sub>3</sub>:Eu(2%) thin film grew in a high density of similar granulated nano-size, which made it have a relatively smooth surface morphology. Conversely, Ga<sub>2</sub>O<sub>3</sub>:Eu(5%) thin film grew with bigger grain size and has rough surface morphology. Both reflectance and transmittance intensity spectra of Ga<sub>2</sub>O<sub>3</sub>:Eu(2%) thin film were higher than those of Ga<sub>2</sub>O<sub>3</sub>:Eu(5%) thin film. Variation of Eu doping concentration did not change the optical bandgap of the growing films. The optical bandgaps of undoped Ga<sub>2</sub>O<sub>3</sub> film and Ga<sub>2</sub>O<sub>3</sub>:Eu film are relatively similar, i.e., 3.4 eV. The existence of Eu(2%) doping in the Ga<sub>2</sub>O<sub>3</sub> configuration leads the luminescence peak shift to the shorter wavelength region (blueshift). In contrast, the presence of Eu(5%) doping leads the luminescence peak shift to the longer wavelength region (redshift). Photoluminescence emissions of all samples were observed in the red region with the emission peak at the range of 593 to 602 nm.

## Methods

Ga<sub>2</sub>O<sub>3</sub>:Eu thin films were grown using DC magnetron sputtering (homemade). The scheme of DC magnetron sputtering system is shown in Figure 8. Ga<sub>2</sub>O<sub>3</sub> (99.999%) and Eu(III) oxide (99.999%) powders were used as pellet-made materials. Eu(2%) and Eu(5%) were used as doping elements in the production of Ga<sub>2</sub>O<sub>3</sub>:Eu(2%) and Ga<sub>2</sub>O<sub>3</sub>:Eu(5%) pellets. Si(100) wafer and corning glass were used as substrate. High-purity argon (Ar) and oxygen (O<sub>2</sub>) were used as sputter gas and dilute gas during deposition process. The growth process of Ga<sub>2</sub>O<sub>3</sub>:Eu thin films were done in three main steps. The first step was the fabrication of Ga<sub>2</sub>O<sub>3</sub>:Eu target. In this process, Ga<sub>2</sub>O<sub>3</sub> and Eu(III) oxide powders were milled and mixed, and were then pressed to form the rigid Ga<sub>2</sub>O<sub>3</sub>:Eu target (pellet). Ga<sub>2</sub>O<sub>3</sub>:Eu pellet was then sintered at 900°C for 3 h. Ga<sub>2</sub>O<sub>3</sub>:Eu(2%) target and Ga<sub>2</sub>O<sub>3</sub>:Eu(5%) target were produced by varying the concentration of Eu doping in the mixing process with Ga<sub>2</sub>O<sub>3</sub> powders. The second stage was substrate preparation. Si(100) and corning glass substrates were cut into 1 × 1 cm<sup>2</sup> and

washed using acetone and methanol in ultrasonic bath for 10 min and 5 min, respectively. The substrates were then cleaned using deionized water (DI water) and, after that, were immersed in 10% HF solution. Next, they were re-cleaned using DI water and subsequently blow-dried with nitrogen (N<sub>2</sub>). The final stage was the growth process of Ga<sub>2</sub>O<sub>3</sub>:Eu thin films. In this process, the substrate was placed on the anode, while the target was put on the cathode. Ga<sub>2</sub>O<sub>3</sub>:Eu thin films were grown on Si (100) and corning glass substrates under oxygen flow with plasma power variation. During the growing time, the growth temperature and argon gas pressure were set at 3 h, 600°C, and 600 mTorr, respectively. The morphology and chemical composition of the growing films were analyzed using SEM and EDX. The optical properties of the film were then analyzed using UV-vis spectrophotometer and PL spectrometer.

## Competing interests

The authors declare that they have no competing interests.

## Authors' contributions

PM participated in the coordination of the study, preparation and growth of the samples as well as drafting the manuscript. SS participated in the growth and characterization of the samples. EW participated in the characterization, analysis of the data, and editing the manuscript. All authors read and approved the final manuscript.

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